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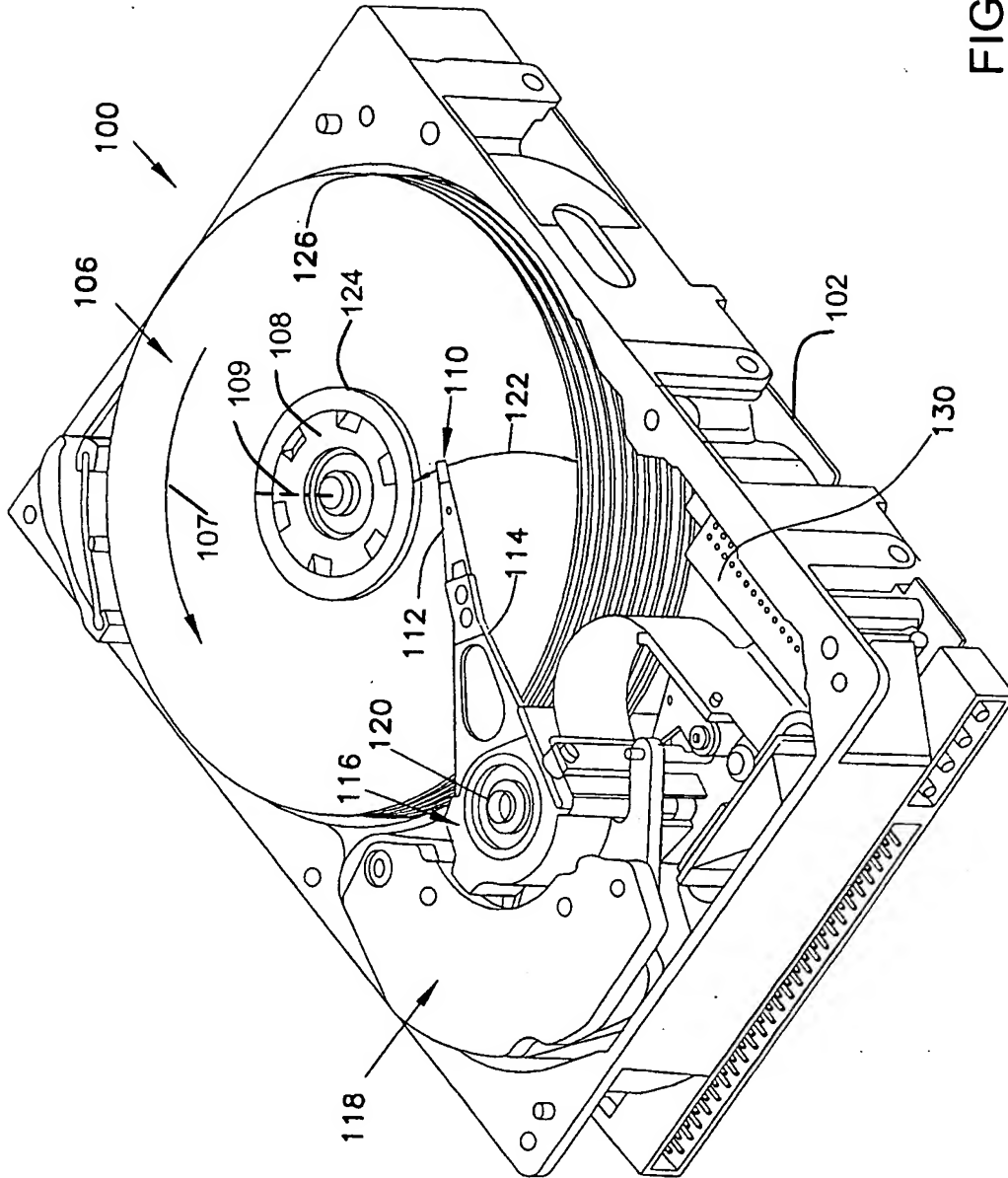


FIG. 1

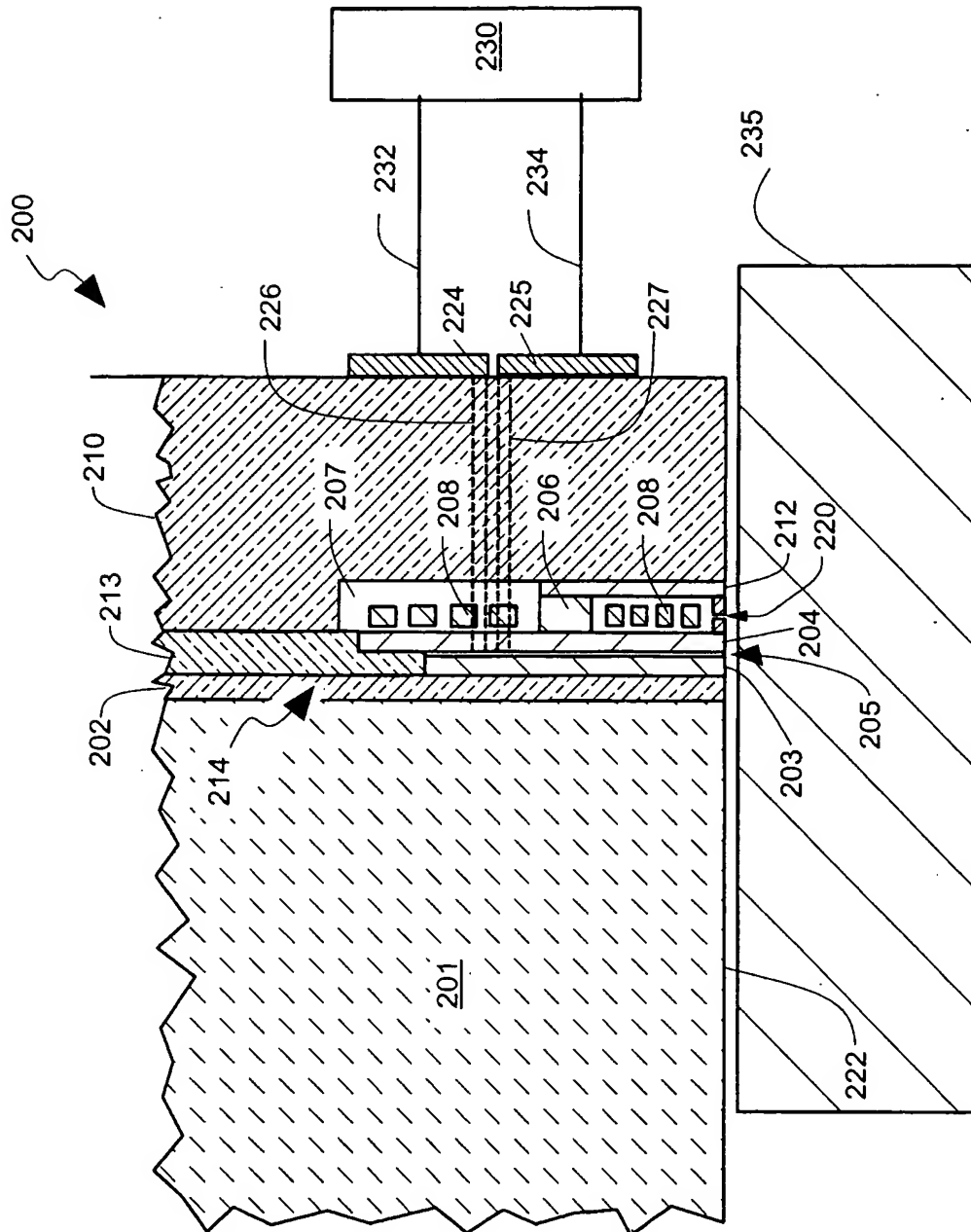


FIG. 2

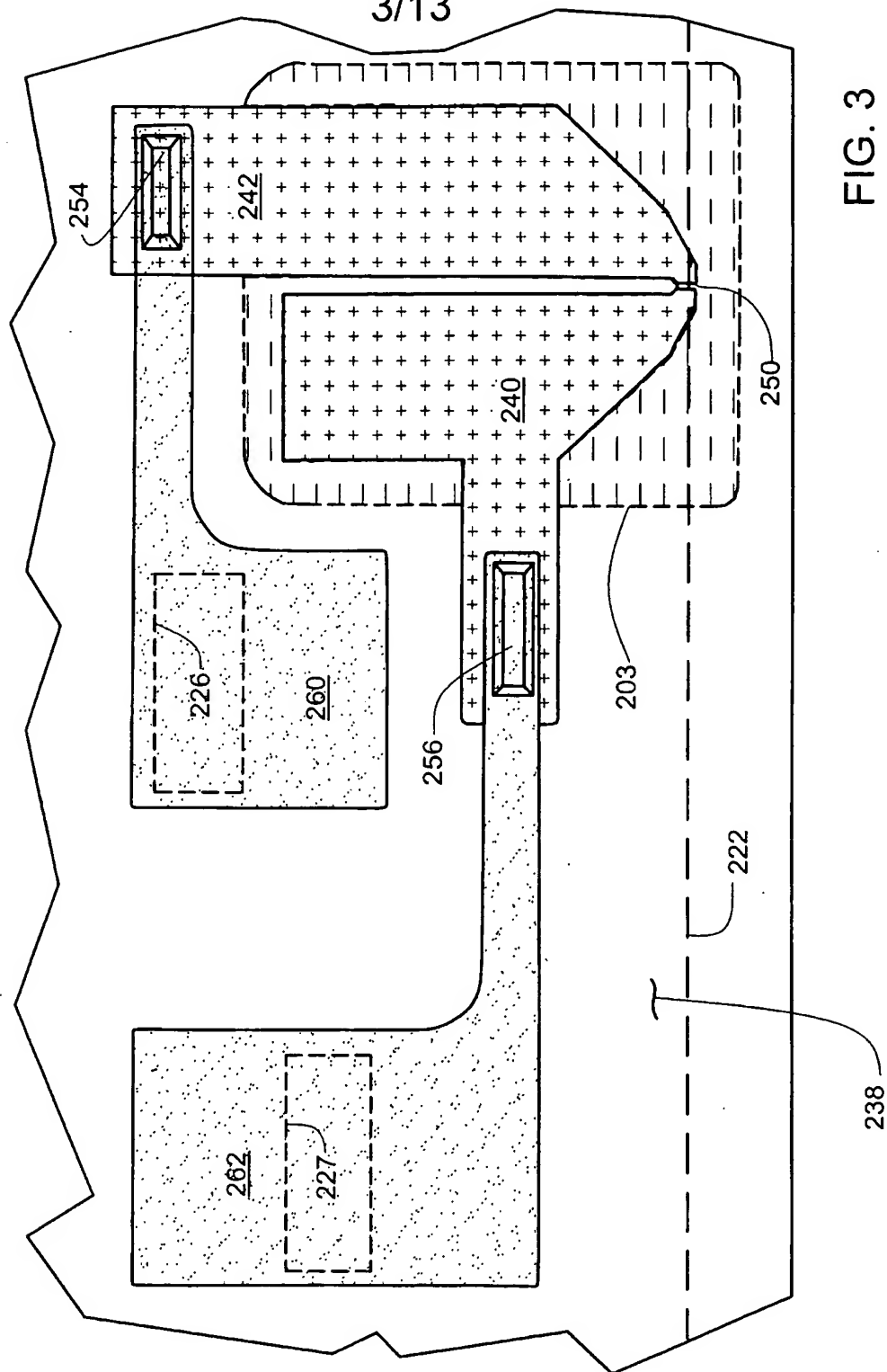


FIG. 3

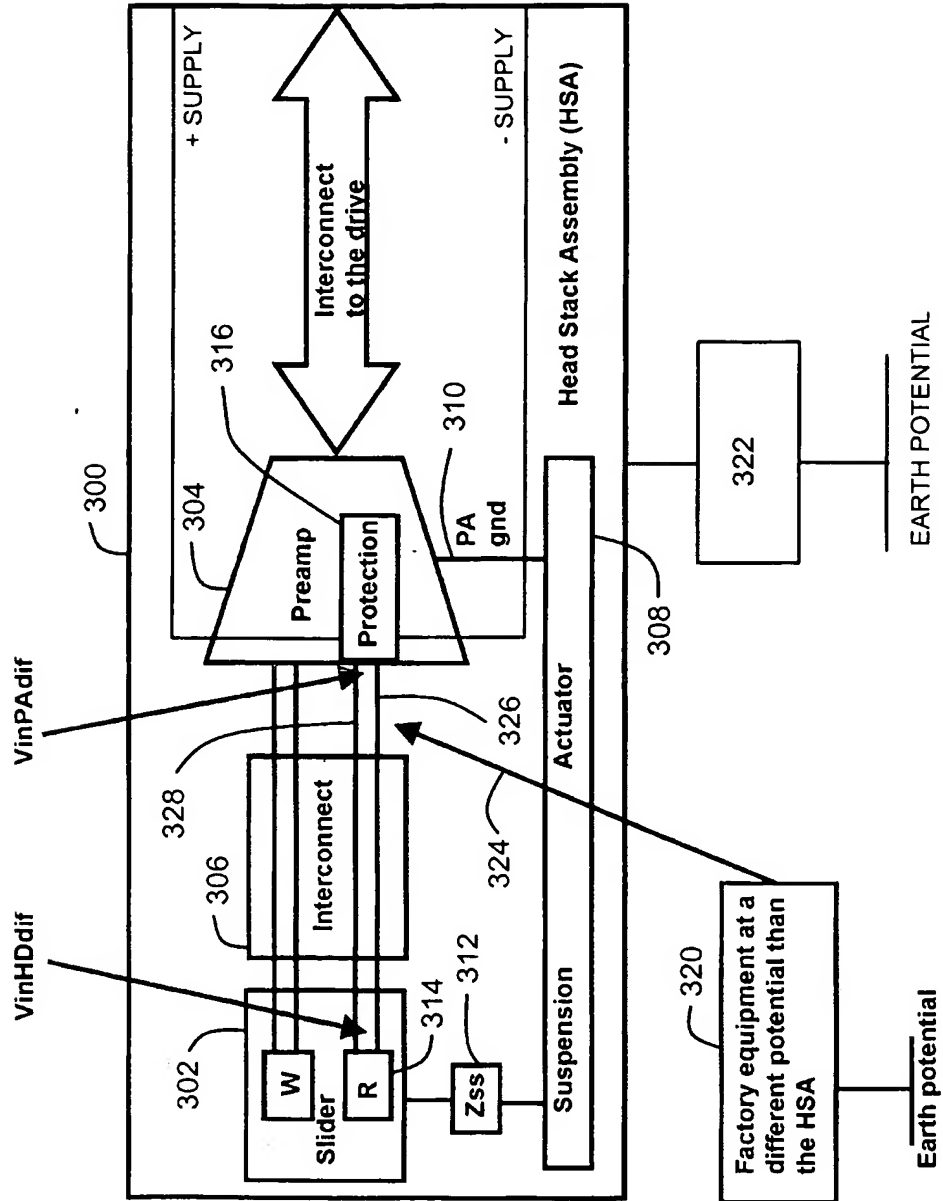
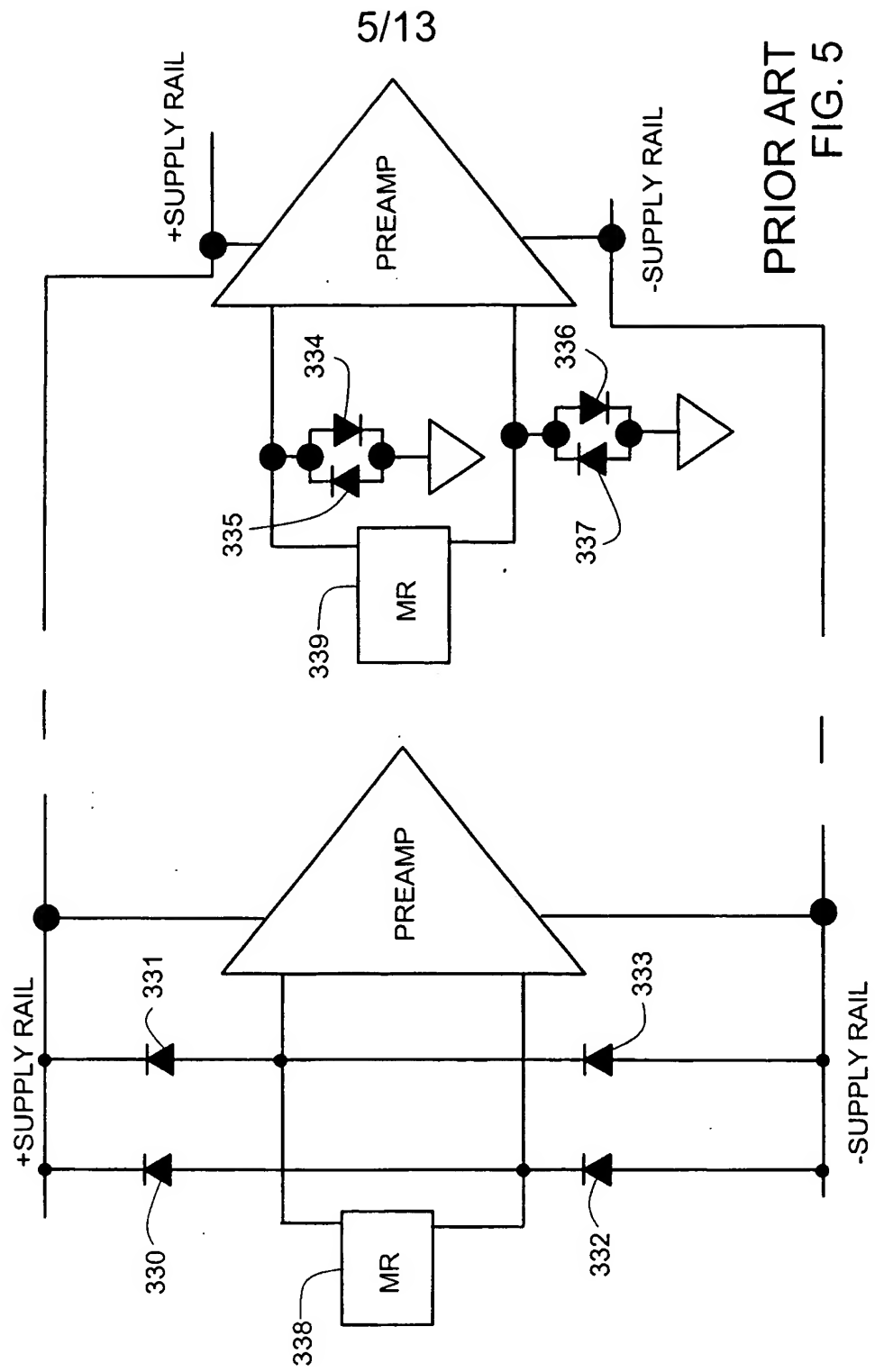


FIG. 4



PRIOR ART  
FIG. 5

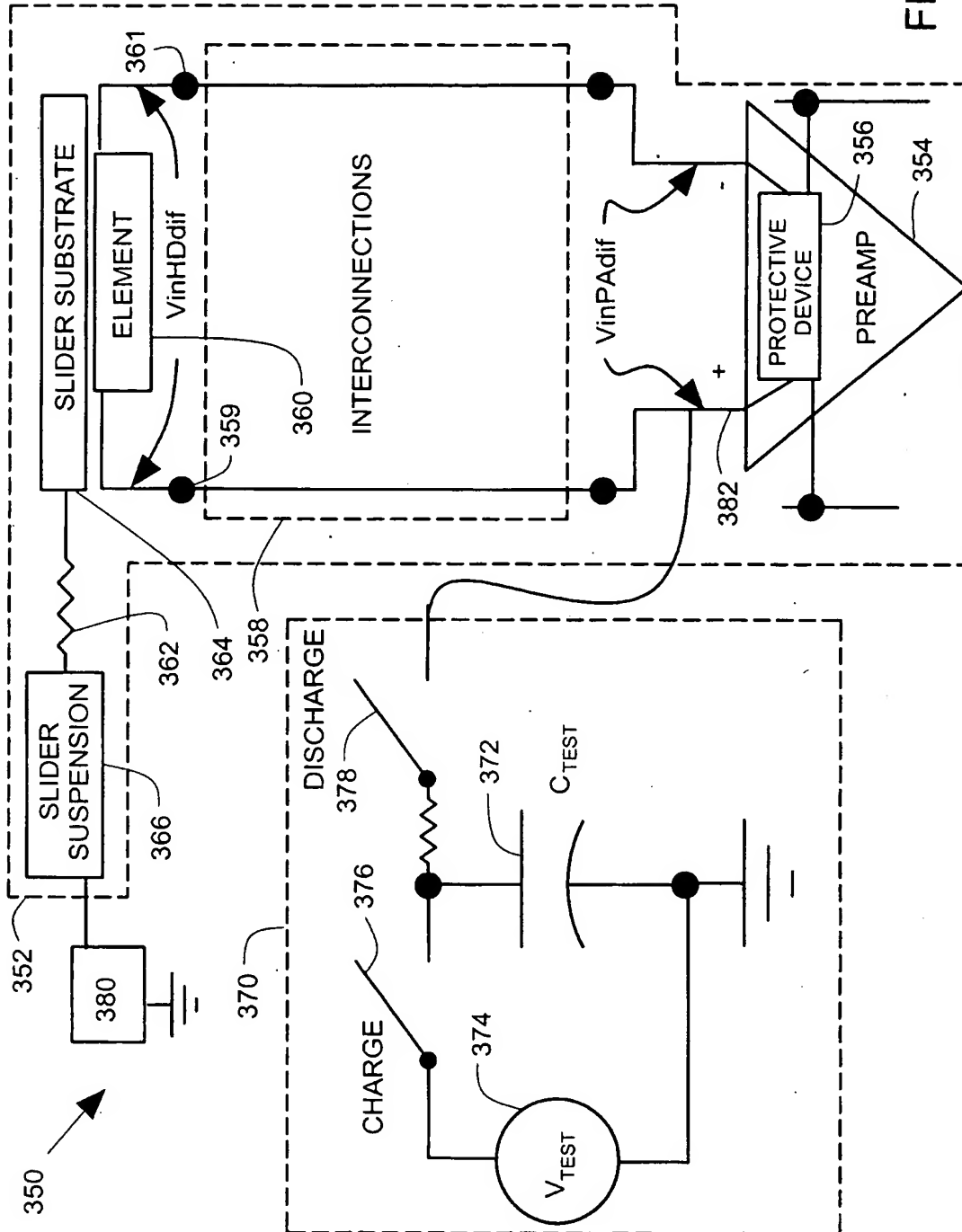


FIG. 6

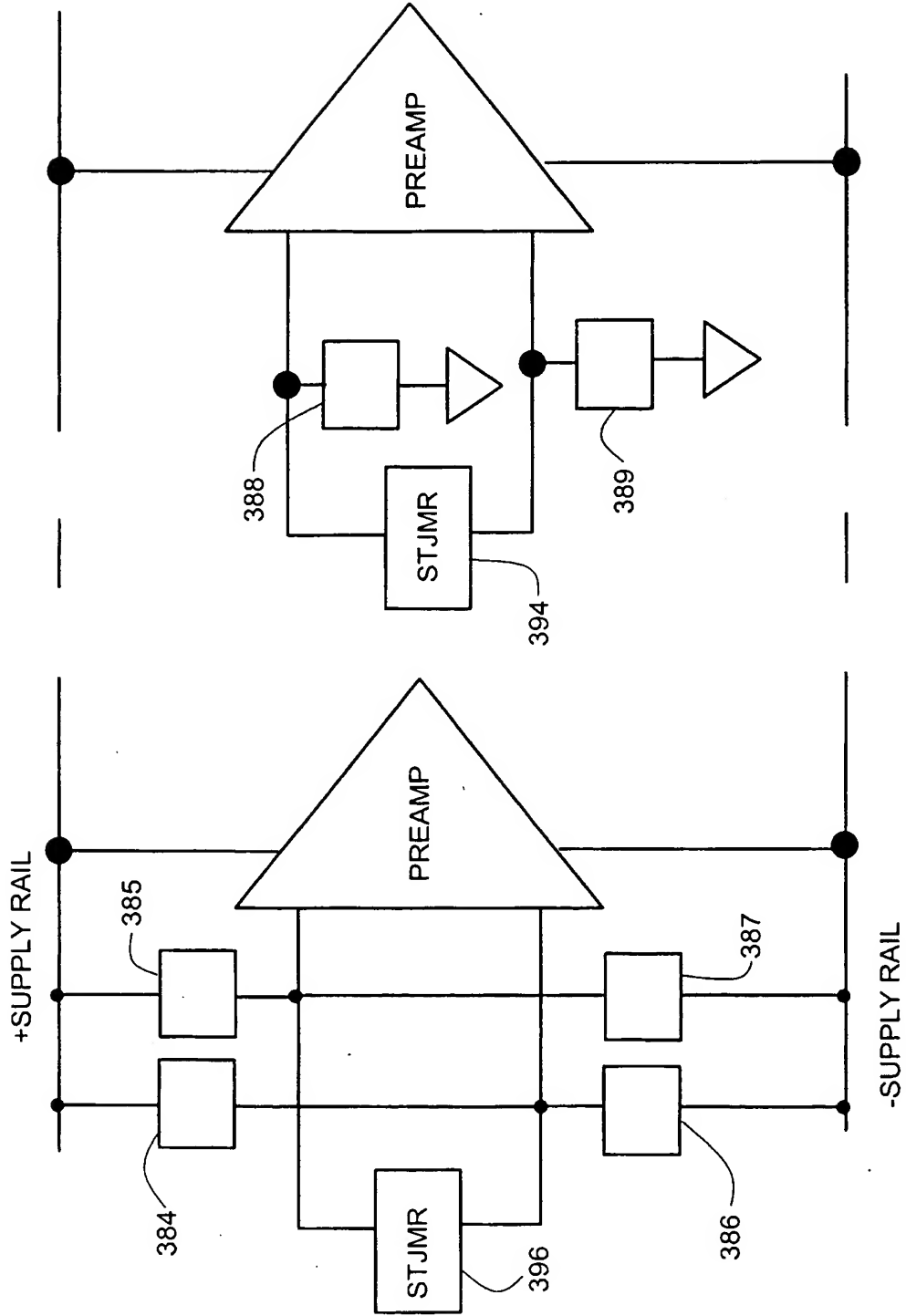


FIG. 7



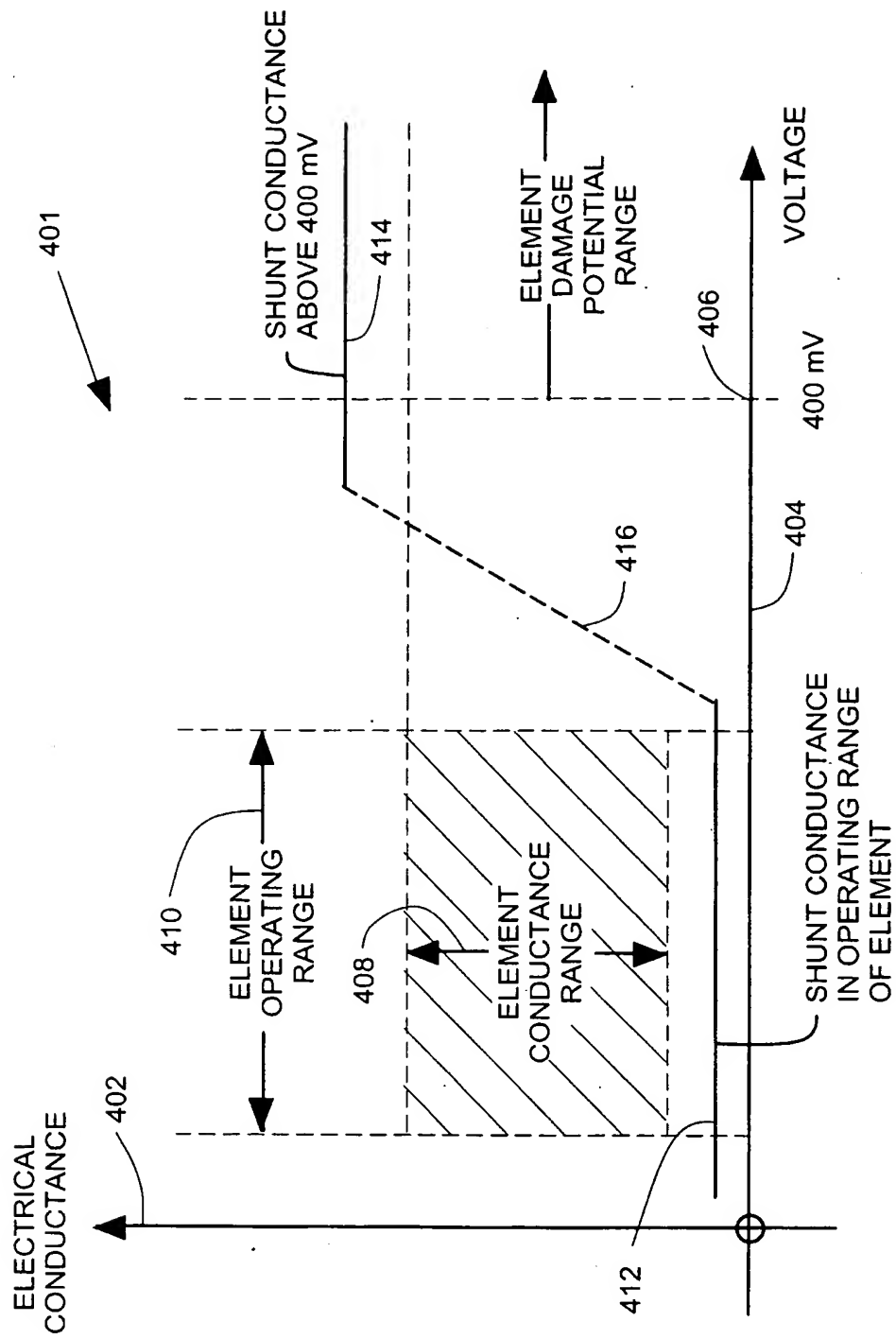


FIG. 8

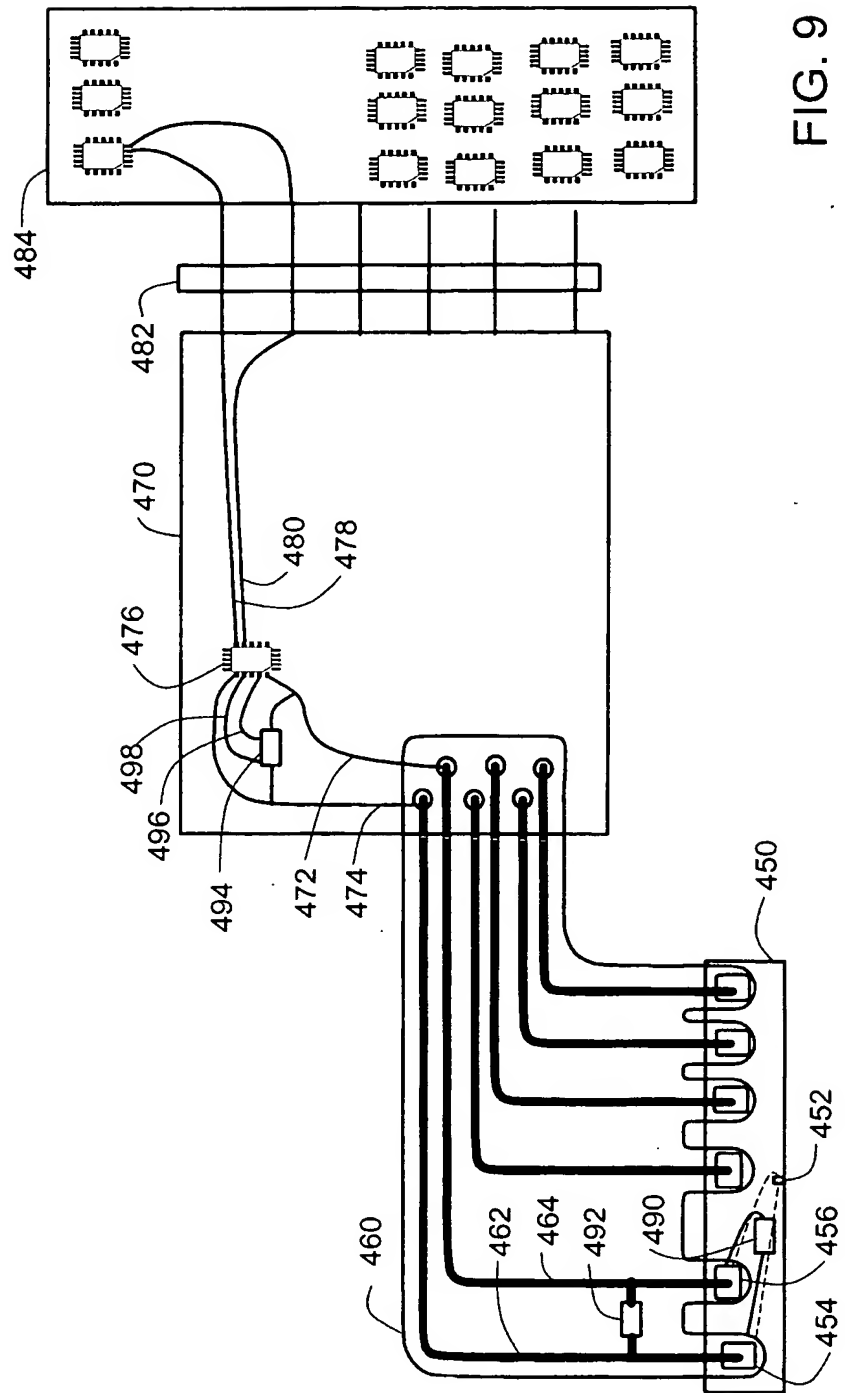
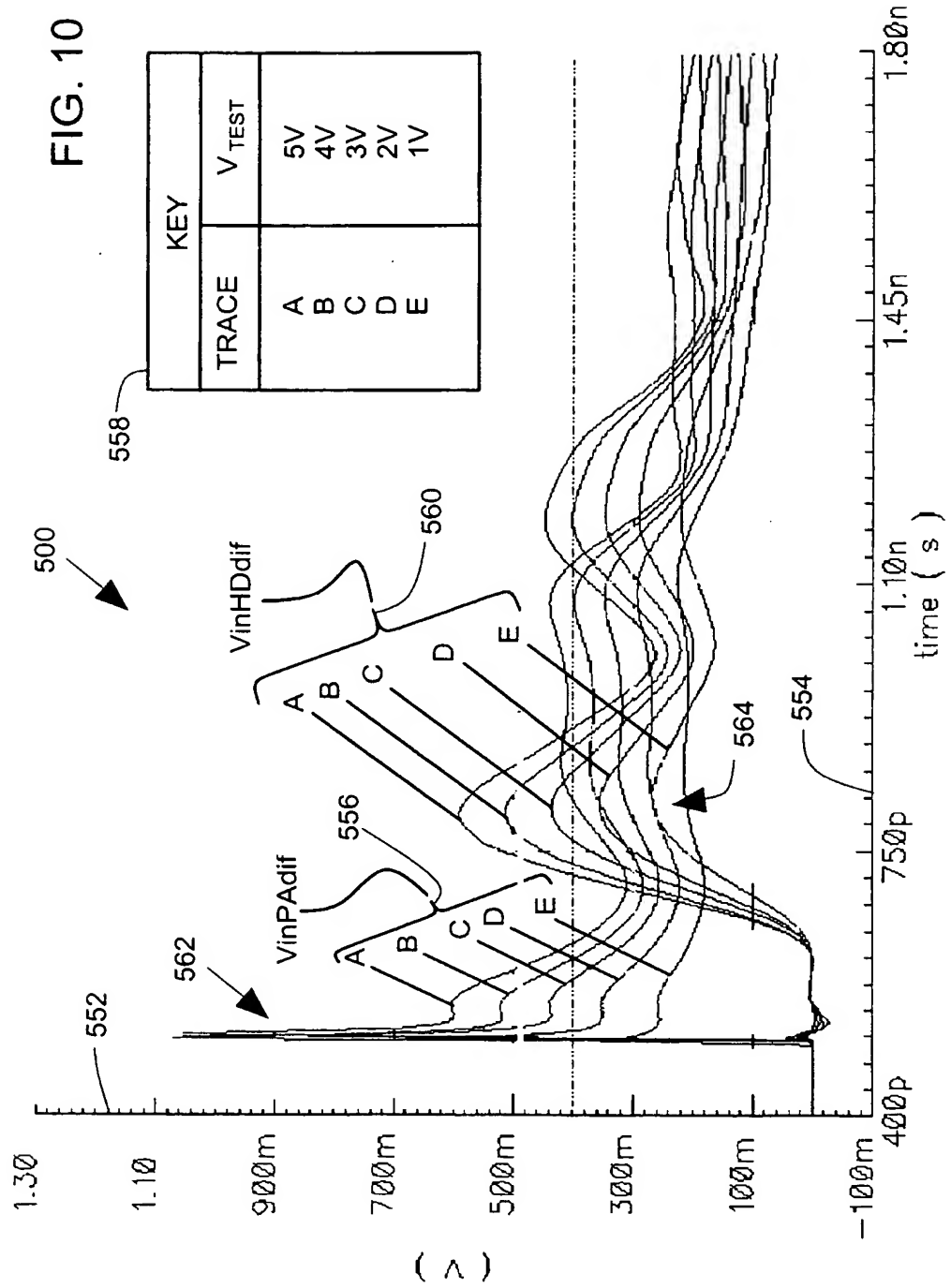


FIG. 9



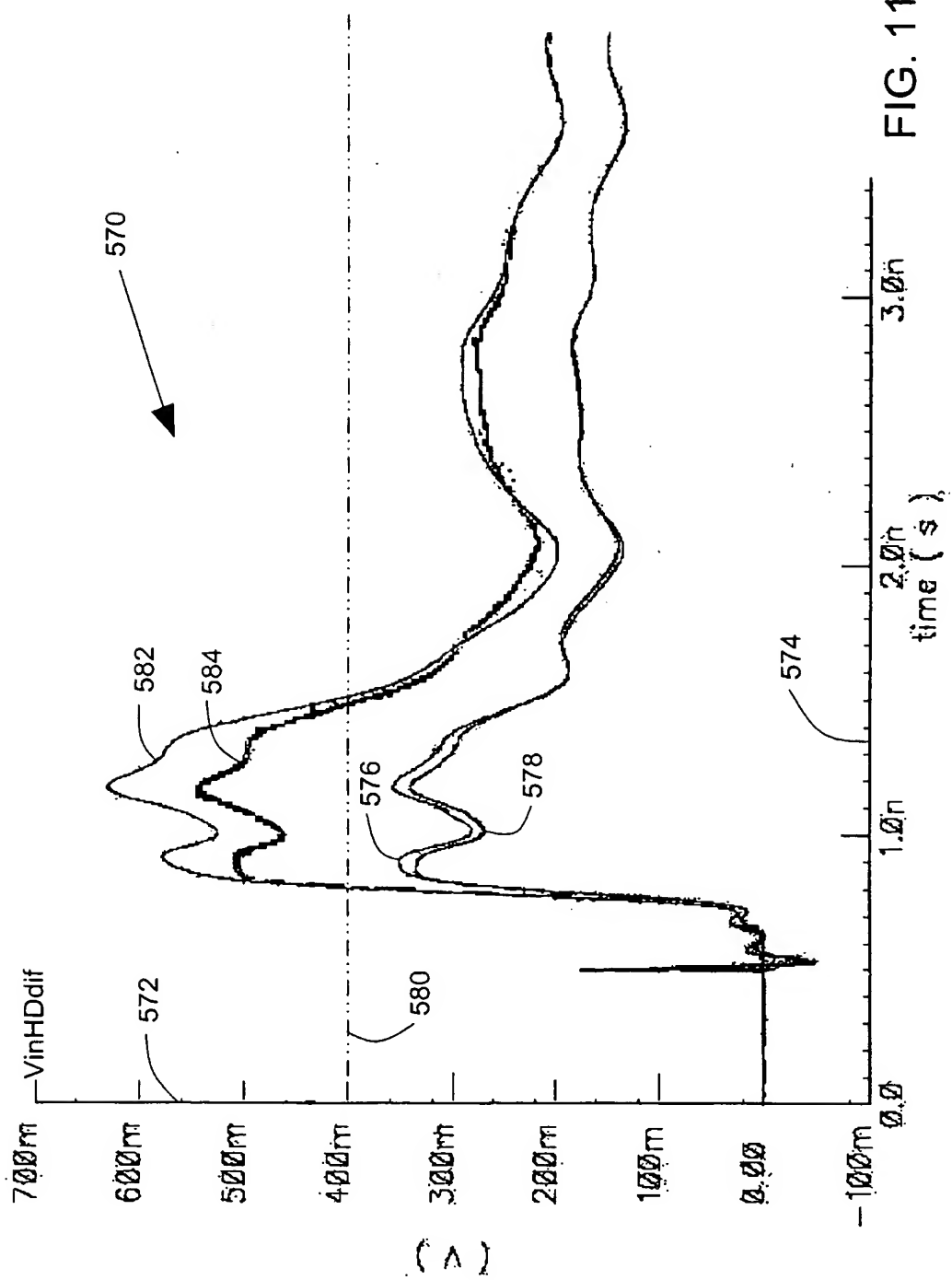


FIG. 11

Schottky metal    *Anode*

590

*Schottky*

N-epi  
N+ substrate  
*Cathode*

Schottky metal/  
Ohmic contact    *Anode*

594

*JBS*

N-epi  
N- substrate  
*Cathode*

Junction Schottky Barrier

Schottky  
contact    *Anode*

596

N- epi    TMBS     $\text{SiO}_2$

N+ substrate  
*Cathode*

Trench MOS Schottky Barrier

FIG. 12

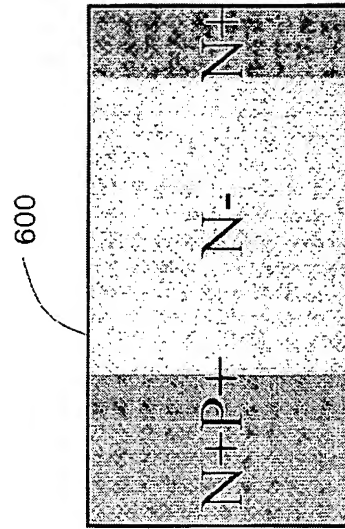


FIG. 13